



GTS NANO-DEVICE SIMULATOR

THE TRUE* PHYSICAL MODELING SOLUTION



- DEEP INSIGHT, AS NEVER SEEN IN TCAD BEFORE
- UNRIVALED ACCURACY AND NUMERICAL EFFICIENCY
- QUICK FAMILIARIZATION, FAST RESULTS

High-Performance CMOS Logic

S-RAM D-RAM

NOR Flash NAND Flash

SONOS 3D NAND

Integrated materials database
Import from ab-initio simulation

Material Crystal orientation

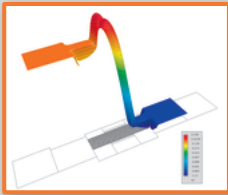
Geometry, Doping

Stress / Strain

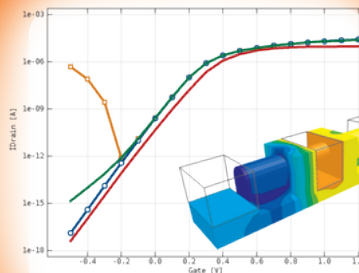
Import GDSII or from process
SWB integration
Unstructured grids

Under the barrier: I_{OFF}

Tunneling transport
Non-local 2D/3D QTBM model
Band-to-band & direct tunneling
SD & Gate barrier, leakage



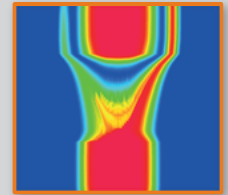
I_{OFF}



PHYSICAL DEVICE SIMULATION

Over the barrier: I_{ON}

Phase-space transport
Solving sub-band BTE, $k \cdot p$ based
Holes & electrons - NMOS/PMOS
Ballistic transport & scattering

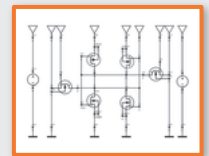


I_{ON}

- Shrinking, path-finding
- Performance
- Reliability, variability
- Increasing yield

Compact model extraction

Built-in circuit simulation
Mixed mode
Circuit reliability and variability



- 8 years of leading-edge experience
- In-house scientific research, with over 150 papers at IEDM, ESSDERC, SISPAD,...

- Consistent, integrated framework
- Import/export of industry standard files
- Grid and cloud support
- Acclaimed user interface



7/5nm Nanowire

14/10nm FinFET

UTB FD SOI

Tunnel FET

InGaAs InAlAs

SiGe

GTS NDS – SUPERIOR TOOLS FOR SUPERIOR TECHNOLOGY

*Capturing all physical effects relevant for nano device performance, variability, and reliability



Predictions based on physics.



GTS Nano-Device Simulator

THE TRUE* PHYSICAL MODELING SOLUTION

NDS in Path-Finding

- Examine new architectures / novel channel materials for N7, N5
- Rely on physically sound predictions based on material properties
- Make profound decisions, understanding physical phenomena

NDS in Device Scaling and Introducing New Technologies

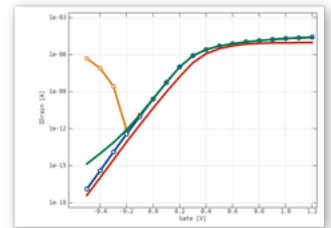
- Rely on predictive simulation for your future technology nodes
- Efficiently introduce and optimize FinFET / FD-SOI for N10 / N14
- Port parameters across technologies (for instance N22 to N14)
- Exploit the opportunities of an extended prediction window

NDS in Performance Optimization for Logic and Memory Applications

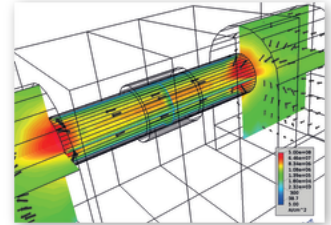
- Evaluate technologies for various applications with real physics
- Optimize performance on device and circuit level
- Study variability and reliability on device and circuit level

NDS in PDK Development

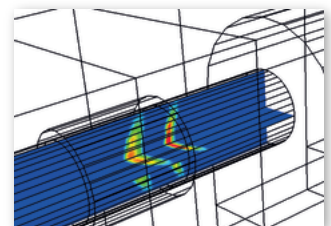
- Know your current and future platforms
- Evaluate technologies at early stages, on device and circuit level
- Benefit from Design-Technology Co-Optimization (DTCO)
- Extract parameters for compact models



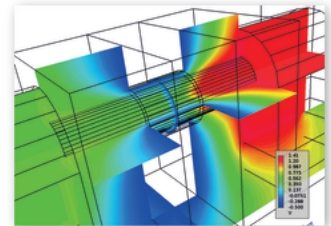
NMOS I/V curve calculated by NDS' predictive physical models



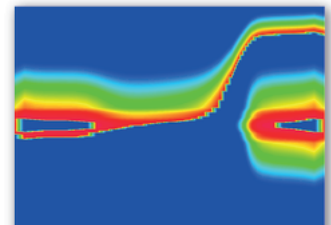
8nm NMOS, current density



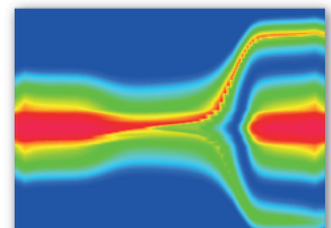
8nm NMOS, effective generation rate due to BtB tunneling



8nm NMOS, potential profile



8nm PMOS, ballistic distribution function in phase space



8nm PMOS, dissipative distribution function in phase space

What makes the Difference

NDS integrates all models to simulate transistor performance:

Drive Current – Boltzmann Transport – I_{ON}

- Realistic band structure / phase-space approach
- Ballistic and dissipative transport for NMOS and PMOS
- Full coverage of confinement, orientation, strain
- Velocity overshoot, quantum resistance, ballisticity
- Adaptive algorithms – fastest code on the market

Off-State Leakage – Tunneling Transport – I_{OFF}

- Quantum-mechanical transport (QTBM)
- Full coverage of confinement, non-locality, band-gap widening
- Direct gate, source-to-drain and band-to-band leakage
- Sub-threshold slope, off-current bounce

Ready for New Materials – strained Si, SiGe, Ge, III/V

- Customer-editable materials database, import atomistic data

Integration / Industry-Standard Interfaces

- GDSII import, SWB integration, unstructured grids



SUPERIOR TOOLS FOR SUPERIOR TECHNOLOGY

GTS NDS includes models and techniques published by GTS researchers at IEDM 2015 and IEDM 2016

